Session Title:	[WeE3] Plasma Source Technology
Session Date:	November 13 (Wed.), 2024
Session Time:	16:05-17:35
Session Room:	Room E (Sicily Room, 1F, Paradise Hotel Busan)
Session Chair:	Prof. Ho-Jun Lee (Pusan Nat'l Univ., Korea)

[WeE3-1] [Invited] 16:05-16:35

Advances in Pulsed RF Power Delivery for Plasma Processes

Steven Shannon (North Carolina State Univ., USA)

[WeE3-2] 16:35-16:55

Charge-Free Plasma Processing Using Ultra-Low Electron Temperature Plasma for Atomic Scale Semiconductor Devices

Min-Seok Kim, Na Yeon Kim, Junyoung Park, and Chin-Wook Chung (Hanyang Univ., Korea)

[WeE3-3] 16:55-17:15

Microwave Heating Techniques in Wafer Processing: Utilizing Toroidal Slot Antennas and Resonant Cavity Modes

Sung-Hyeon Jung, Sang-Woo Kim (Pusan Nat'l Univ., Korea), Ju-Hong Cha (Gyeongsang Nat'l Univ., Korea), and Ho-Jun Lee (Pusan Nat'l Univ., Korea)

[WeE3-4] 17:15-17:35

Enhancement of Plasma Characteristics by Using 2.45[GHz] Microwave Source in Inductively Coupled Plasma

Dong-Jin Kang, Sang-Woo Kim (Pusan Nat'l Univ., Korea), Ju-Hong Cha (Gyeongsang Nat'l Univ., Korea), and Ho-Jun Lee (Pusan Nat'l Univ., Korea)